

Title (en)
COMPOSITIONS FOR MICROLITHOGRAPHY

Title (de)
ZUSAMMENSETZUNGEN FÜR DIE MIKROLITHOGRAPHIE

Title (fr)
COMPOSITIONS POUR MICROLITHOGRAPHIE

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Application
EP 01987900 A 20011016

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Abstract (en)
[origin: WO0233489A2] A fluorine-containing polymer prepared from at least a spacer group selected from the group consisting of ethylene, alpha-olefins, 1,1'-disubstituted olefins, vinyl alcohols, vinyl ethers, and 1,3-dienes; and a norbornyl radical containing a functional group containing the structure: -C(Rf)(Rf')Orb wherein Rf and Rf' are the same or different fluoroalkyl groups of from 1 to about 10 carbon atoms or taken together are (CF2)n wherein n is an integer ranging from 2 to about 10 and Rb is a hydrogen atom or an acid- or base-labile protecting group; r is an integer ranging from 0-4. The fluorine-containing polymer has an absorption coefficient of less than 4.0 mm⁻¹ at a wavelength of 157 nm. These polymers are useful in photoresist compositions for microlithography. They exhibit high transparency at this short wavelength and also possess other key properties, including good plasma etch resistance and adhesive properties.

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